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Advanced PECVD-SiO2				LPD after 5min pump down			Thickness	Index
	5/8/12	wafer1	965	985	not done	not done		
		wafer2	587	620	not done	not done		
		wafer3	465	495	not done	not done		
		wafer4	340		not done	232	2924.73	1.469
		wafer5	221		not done	237	2918.89	1.468
	Date	wafer#	LPD count before	LPD after 5min pump down	LPD after 5min SIO2 coat	LPD after SiO2 deposition	Thickness	Index
	5/24/12	wafer6	119	200	not done	344	986.03A	1.476
	6/4/12	wafer7	368	368	not done	904	974.45A	1.474
	Date	wafer#	LPD count before	LPD after 5min pump down	LPD after 10min SIO2 coat	LPD after SiO2 deposition	Thickness	Index
	6/14/12	wafer8	349	318	not done	1419**	2849.26A	1.471
		wafer9	243	137	not done	not done		
		wafer10	154	424*	not done	not done		
Comment:* Few group:	s of small p	articles, *	* A lot of small part	icles				
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